

## Band offsets and heterostructures of two-dimensional semiconductors

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The band offsets and heterostructures of monolayer and few-layer transition-metal dichalcogenides  $\text{MX}_2$  ( $M = \text{Mo}, \text{W}$ ;  $X = \text{S}, \text{Se}, \text{Te}$ ) are investigated from first principles calculations. The band alignments between different  $\text{MX}_2$  monolayers are calculated using the vacuum level as reference, and a simple model is proposed to explain the observed chemical trends. Some of the monolayers and their heterostructures show band alignments suitable for potential applications in spontaneous water splitting, photovoltaics, and optoelectronics. The strong dependence of the band offset on the number of layers also implicates a possible way of patterning quantum structures with thickness engineering. © 2013 American Institute of Physics. [<http://dx.doi.org/10.1063/1.4774090>]

After graphene became experimentally accessible in 2004,<sup>1</sup> two-dimensional (2D) materials have attracted great attention mainly due to their unique physical properties and capability to fulfill the demands of future nanoelectronic industry on flexibility, adaptability, and multi-functionality.<sup>2</sup> Transition metal dichalcogenides  $\text{MX}_2$  (where  $M$  and  $X$  correspond to transition metal and chalcogen, respectively) are members of the layered materials like graphite. Soon after the discovery of graphene, it was demonstrated that monolayer  $\text{MX}_2$ , such as  $\text{MoS}_2$  and  $\text{NbSe}_2$ , could also be achieved using mechanical exfoliation.<sup>3</sup> More recently, various experimental studies have reported the synthesis of  $\text{MX}_2$  monolayers, such as  $\text{MoS}_2$ ,  $\text{WS}_2$ ,  $\text{MoSe}_2$ ,  $\text{MoTe}_2$ ,  $\text{TiS}_2$ ,  $\text{TaS}_2$ ,  $\text{TaSe}_2$ ,  $\text{NiTe}_2$ , and  $\text{ZrS}_2$ .<sup>4–6</sup> Bulk  $\text{MoX}_2$  and  $\text{WX}_2$  are indirect band-gap semiconductors, whereas their monolayers have direct bandgaps,<sup>7–9</sup> which are favorable for optoelectronic applications. The existence of the native bandgap provides an excellent current on/off ratio of  $10^8$  in single-layer  $\text{MoS}_2$  based field-effect transistors,<sup>10</sup> and the application of monolayer  $\text{MoS}_2$  in integrated circuits and logic operations has already been realized.<sup>11</sup>

Recently, the band structure of single- and few-layer  $\text{MX}_2$  has been studied using first principles *ab-initio* calculations, focusing mostly on their bandgap values, while their band offsets are much less explored. Band offsets of semiconductors are important and necessary parameters in material and device design. More specifically, the band offset is critical to many properties such as quantum confinement,<sup>12</sup> dopability,<sup>13</sup> and chemical activity.<sup>14</sup> Moreover, designing heterostructure devices based on 2D semiconductors requires accurate band offset parameters across different materials. Heterojunctions interfacing different 2D materials would enable the so-called van der Waals epitaxy,<sup>15</sup> in which the lattice matching condition in traditional epitaxy is drastically relaxed, allowing the formation of a wide range of 2D/2D, 2D/3D, or even more advanced 3D/2D/3D heterostructures. Finally, chemical trends of the band offsets provide a useful tool for predicting physical properties of materials and heterostructure

geometries. Previously, the band offset between several bulk  $\text{MX}_2$  has been investigated by Jiang.<sup>16</sup> However, due to the quantum confinement effect, the physical properties of the 2D semiconductors are very different compared to their 3D counterparts, and therefore the band offsets of single layer  $\text{MX}_2$  are expected to show stark differences from the 3D case. So far, band offsets of monolayer  $\text{MX}_2$  are completely unknown. In this work, we study the electronic properties of  $\text{MX}_2$  monolayers and few layers ( $M = \text{Mo}, \text{W}$ , and  $X = \text{S}, \text{Se}, \text{Te}$ ) using first principles calculations, but focus on their band offsets and interesting heterostructure geometries enabled by the band offsets. On the basis of the observed chemical trends, we discuss implications for potential device applications.

The calculations were performed using the Vienna *ab initio* simulation package (VASP).<sup>17</sup> The six outermost electrons for transition-metal and chalcogen were treated as valence electrons. The core-valence interaction was described by the frozen-core projector augmented wave (PAW) method.<sup>18</sup> The generalized gradient approximation of Perdew-Burke-Ernzerhof (GGA-PBE)<sup>19</sup> was adopted for exchange-correlation functional. Part of the calculations were also performed using the Heyd-Scuseria-Ernzerhof (HSE06) hybrid functional.<sup>20</sup> Energy cut off for plane-wave expansion was set to 400 eV. Brillouin zone sampling was performed with Monkhorst-Pack (MP) special k point meshes.<sup>21</sup> For the hexagonal unit cell, a grid of  $24 \times 24 \times 1$  was used ( $24 \times 24 \times 5$  in bulk calculations), and the k-point grid scaled with respect to the supercell size. A vacuum layer larger than  $10 \text{ \AA}$  was added to avoid interaction between adjacent images. All atoms were allowed to relax until the calculated Hellmann-Feynman force on each atom was smaller than  $0.01 \text{ eV/\AA}$ . Spin-orbit interaction (SOI) is included when calculating band structures. The vacuum level was taken as zero reference in the calculations of band alignment.

The monolayers of  $\text{MX}_2$  considered in this work have hexagonal lattices with honeycomb structures (1H- $\text{MX}_2$ ) similar to graphene. Basic lattice parameters and physical properties of single-layer  $\text{MX}_2$  are listed in Table I, and the calculated bandgap values are consistent with previous studies.<sup>9,22</sup> Figure 1 shows the calculated band structure of

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TABLE I. Calculated properties of  $\text{MX}_2$  monolayers: lattice constant  $a$ , M-X bond length  $d$ , bandgap  $E_g$ , spin-orbit splitting  $\Delta_{SO}$  in valence band, cohesive energy  $E_C$  per unit cell, charge transfer  $\Delta\rho$  of the M atom, Poisson's ratio  $\nu$ , and in-plane stiffness  $C$ .  $a$ ,  $d$ ,  $E_g$ , and  $\Delta_{SO}$  calculated by HSE06 are also shown.

	$a$ (Å)	$a^{\text{HSE}}$ (Å)	$d$ (Å)	$d^{\text{HSE}}$ (Å)	$E_g$ (eV)	$E_g^{\text{HSE}}$ (eV)	$\Delta_{SO}$ (eV)	$\Delta_{SO}^{\text{HSE}}$ (eV)	$E_C$ (eV)	$\Delta\rho$ (e)	$\nu$	$C$ (N/m)
MoS <sub>2</sub>	3.18	3.16	2.41	2.40	1.59	2.02	0.15	0.20	15.31	1.09	0.25	124.24
MoSe <sub>2</sub>	3.32	3.29	2.54	2.51	1.33	1.72	0.19	0.27	13.70	0.85	0.23	103.40
MoTe <sub>2</sub>	3.55	3.52	2.73	2.70	0.94	1.28	0.22	0.35	12.01	0.52	0.24	78.90
WS <sub>2</sub>	3.18	3.16	2.42	2.40	1.55	1.98	0.43	0.56	17.28	1.24	0.22	139.54
WSe <sub>2</sub>	3.32	3.29	2.55	2.53	1.25	1.63	0.47	0.63	15.45	0.96	0.19	115.52
WTe <sub>2</sub>	3.55	3.52	2.74	2.71	0.75	1.03	0.49	0.69	13.51	0.57	0.18	86.93

MoS<sub>2</sub>, MoSe<sub>2</sub>, and WS<sub>2</sub>. While the lattice constants of monolayer  $\text{MX}_2$  calculated by HSE06 are in excellent agreement with known bulk values, those obtained by PBE are slightly overestimated. Despite this slight discrepancy, we note that these two methods provide similar physical trends; i.e., when X goes from S to Te, the lattice constant and bond length of  $\text{MX}_2$  increase associated with the increase in ionic radius of X. We also note that the lattice constants of  $\text{MoX}_2$  and  $\text{WX}_2$  are very close to each other, indicating that synthesizing  $\text{MoX}_2$ - $\text{WX}_2$  heterostructures might allow one to engineer optical and physical properties with minimum structural defects. Finally, elastic parameters which are obtained by fitting the strain-energy relationship of  $\text{MX}_2$  monolayers show that the in-plane stiffness decreases when X changes from S to Te, and M changes from W to Mo. The calculated Poisson's ratios of  $\text{MX}_2$  monolayer are around 0.2, and the Poisson's ratio of  $\text{MoX}_2$  is found to be slightly larger than that of  $\text{WX}_2$ .

Previous studies have shown that  $\text{MX}_2$  monolayers possess direct bandgaps, with the conduction band maximum (CBM) and valence band minimum (VBM) located at the K symmetry points,<sup>7,9</sup> as well as a significant spin-orbit splitting in valence band,<sup>5,23</sup> consistent with our results as listed in Table I. Comparing to the experimental values, we observe that the bandgap values are underestimated by PBE while they are slightly overestimated by HSE06. Here, we note that regardless of the choice of the method (PBE/HSE06), the observed general trends display similar behavior. Therefore, the deviation from the experimentally reported bandgap values can be omitted when comparing the band offsets between  $\text{MX}_2$  monolayers, and hence the chemical trends of band structures of  $\text{MX}_2$  can be properly described by both PBE and HSE06.

The band alignment for  $\text{MX}_2$  monolayers is shown in Fig. 2(a). In the following, we discuss the results in Fig. 2

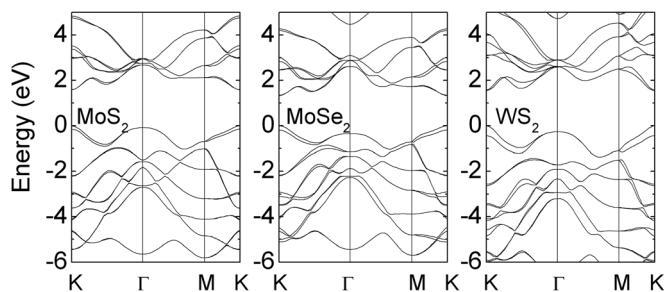


FIG. 1. Band structure of monolayer MoS<sub>2</sub>, MoSe<sub>2</sub>, and WS<sub>2</sub> calculated by PBE.

based on PBE calculations, but similar results can be deduced from the HSE06. Overall, the band offsets show the following trends:

1. As the atomic number of X increases (from S to Te), the energies of CBM and VBM of  $\text{MX}_2$  also increase. Moreover, the conduction band offset (CBO) is smaller than the valence band offset (VBO). More specifically, the VBM of MoSe<sub>2</sub> is 0.63 eV higher than that of MoS<sub>2</sub> while its CBM is 0.37 eV higher than that of MoS<sub>2</sub>. Here, the only exception is WTe<sub>2</sub> where its CBM is slightly lower (by 0.06 eV) than that of WSe<sub>2</sub>.
2. For common-X system, the CBM and VBM of  $\text{WX}_2$  are higher than those of  $\text{MoX}_2$ , i.e.,  $\text{MoX}_2$ - $\text{WX}_2$  lateral heterostructures have a type-II band alignment. For example, the VBM of WS<sub>2</sub> is 0.39 eV higher than that of MoS<sub>2</sub>, and its CBM is 0.35 eV higher.

To understand the observed trends in the band offsets, we look at the physical origin of the observed CBM and VBM values. For simplifying, the following discussions are made based on the band structure calculated without SOI. (SOI only affects the CBM and VBM energies, while the general trends of the band offsets were found to be the same.) Taking MoS<sub>2</sub> as an example, the VBM of MoS<sub>2</sub> mainly consists of the  $d_{x^2-y^2}$  and  $d_{xy}$  orbitals of Mo and the  $p_x$  and  $p_y$  orbitals of S. In addition, it is found that the 5th band at the K points, which locates about 4 eV lower than the VBM, has the same character as VBM. Therefore, the VBM of MoS<sub>2</sub> originates mainly from the repulsion between the  $d_{x^2-y^2}$  and  $d_{xy}$  orbitals of Mo and the  $p_x$  and  $p_y$  orbitals of S. The  $d$  orbital of Mo is higher than the  $p$  orbital of S, so it is pushed up by  $\Delta_1$ , forming the VBM, and the  $p$  orbital is pushed down by  $\Delta'_1$ , as shown in Fig. 2(b). The CBM of MoS<sub>2</sub> has the character of the  $d_{z^2}$  orbital of Mo and the  $p_x$  and  $p_y$  orbitals of S, while the 4th band at the K points, located about 4.5 eV lower than the VBM, has the same character. Thus, the CBM of MoS<sub>2</sub> originates from the repulsion between the  $d_{z^2}$  orbital of Mo and the  $p_x$  and  $p_y$  orbitals of S. The  $d_{z^2}$  orbital is pushed up by  $\Delta_2$ , forming the CBM, and the  $p$  orbital is pushed down by  $\Delta'_2$ . Using this model, we can understand the trends of the band offsets of  $\text{MX}_2$ .

For common-M systems, the VBO and CBO are determined by the repulsion strength  $\Delta_1$  and  $\Delta_2$  between the cation  $d$  orbitals and anion  $p$  orbitals. The magnitude of the repulsion solely depends on the overlap integral of  $d$  and  $p$  orbitals and their difference in energy. In principle, a larger overlap integral or a smaller energy difference leads to larger

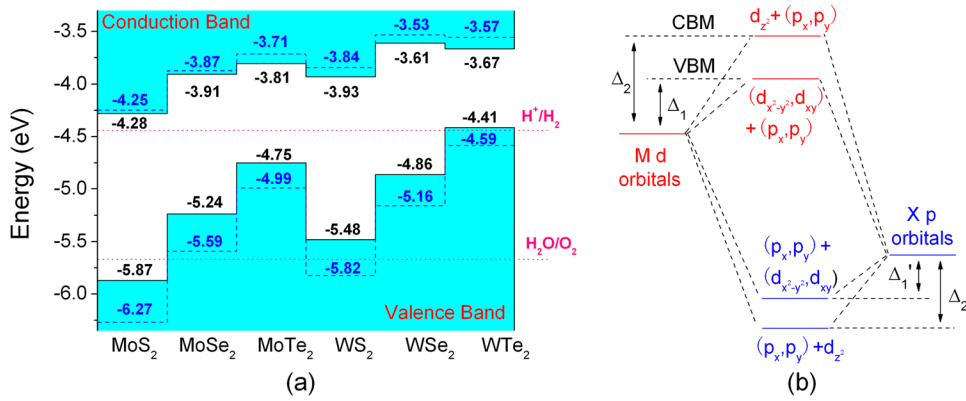


FIG. 2. (a) Calculated band alignment for  $\text{MX}_2$  monolayers. Solid lines are obtained by PBE, and dashed lines are obtained by HSE06. The dotted lines indicate the water reduction ( $\text{H}^+/\text{H}_2$ ) and oxidation ( $\text{H}_2\text{O}/\text{O}_2$ ) potentials. The vacuum level is taken as zero reference. (b) Schematic of the origin of CBM and VBM in  $\text{MX}_2$ .

$\Delta$  value. For increasing X atomic number, its  $p$  orbitals become shallower. As a result, the anion with shallower  $p$  orbitals pushes the cation  $d$  orbitals upwards more than the anion with deeper  $p$  orbitals. As a result,  $\Delta_1$  and  $\Delta_2$  values are larger in systems with larger atomic number of X, and the CBM and VBM would be higher. However, when X goes from S to Te, the M-X bond length also increases. This would lead to a decrease of the overlap integral between the  $d$  and  $p$  orbitals, and partly counteract the increase of  $\Delta_1$  and  $\Delta_2$ . It can be seen from Fig. 2(b) that the repulsion between M  $d_{z^2}$  and X  $p_{x+y}$  orbitals is stronger than that between M  $d_{x^2-y^2} + d_{xy}$  and X  $p_{x+y}$  orbitals, possibly because the former has more  $\sigma$  bonding character while the latter has more  $\pi$  bonding character. Consequently, the influence of the decrease in overlap integral on  $\Delta_2$  is larger than that on  $\Delta_1$ , and the increase of  $\Delta_2$  would be smaller than that of  $\Delta_1$ . The presented interpretation provides an explanation for the general trend that the CBO is smaller than the VBO for common-cation systems. Particularly, W has high  $d$  orbitals, and the M-X bond length of  $\text{WTe}_2$  is the largest among all  $\text{MX}_2$ . As a result, from  $\text{WSe}_2$  to  $\text{WTe}_2$ , the influence of decrease in overlap integral on  $\Delta_2$  overrides the influence of increase in the anion  $p$  orbital energy, and  $\Delta_2$  decreases. So, the CBM of  $\text{WTe}_2$  is lower than that of  $\text{WSe}_2$ .

The trends of band offset between common-X systems can be understood by the position of the  $d$  orbitals of cation. The energy of the  $5d$  orbital of W is higher than that of the  $4d$  orbital of Mo, therefore, the CBM and VBM of  $\text{WX}_2$  are higher than those of  $\text{MoX}_2$ . Figure 2 shows that the band alignment between  $\text{MoX}_2$  and  $\text{WX}_2$  is type-II. In a type-II heterostructure, free electrons and holes will be spontaneously separated, which is suited for optoelectronics and solar energy conversion. Considering such possibility, we provide first calculations on  $\text{MoX}_2$ - $\text{WX}_2$  lateral heterostructures as shown in Fig. 3. We first note that  $\text{MoX}_2$  and  $\text{WX}_2$  have very similar lattice parameters (Table I), allowing one to create

these heterostructures without inducing structural defects. Based on the distribution of charge densities, we observe that the electrons are confined in the  $\text{MoX}_2$ , while the holes are confined in the  $\text{WX}_2$  side. It is, therefore, expected that spontaneous charge separation occurs when excitons diffuse to the  $\text{WX}_2/\text{MoX}_2$  junction, a process that is needed for photovoltaics. In addition, superlattices formed by interfacing alternating  $\text{WX}_2$  and  $\text{MoX}_2$  layers would host mini-bands for quantum devices, and the band offset calculated here would be needed for the design.

It is well established that the bandgap of  $\text{MX}_2$  is sensitive to its thickness,<sup>7</sup> thus its band offset would also be influenced by the thickness. The VBM and CBM positions of  $\text{MX}_2$  for 1, 2, and 4 layers and bulk are shown in Fig. 4. We note that the calculated bulk band alignments are consistent with previous results based on PBE.<sup>16</sup> Generally speaking, as the number of layers is reduced, the VBMs of all  $\text{MX}_2$  move downward (lower in energy), whereas the CBMs move upward (higher in energy), both of which can be understood from a simple quantum confinement effect. However, in some cases such as the VBM of  $\text{WTe}_2$ , this trend is not observed since the SOI, which would lift up the VBM, becomes weaker as the thickness increases. Figure 4 clearly shows that the band edge positions of 2D  $\text{MX}_2$  are drastically different from the bulk cases, especially for  $\text{MoS}_2$  and  $\text{WS}_2$ . Such differences could lead to possible applications of monolayer  $\text{MX}_2$  in fields where their bulk counterparts are not suited. In addition, it is possible to pattern a  $\text{MX}_2$  film into structures where different regions have different number of layers, thus achieving functional quantum devices by mere thickness engineering.

Another example is photo-splitting reactions of water. It is well known that to achieve high efficiency, the photocatalyst should satisfy two main conditions.<sup>24</sup> The first is the presence of an ideal bandgap ( $\sim 2.0\text{eV}$ ) that allows absorption of a large portion of the solar spectrum. Among the

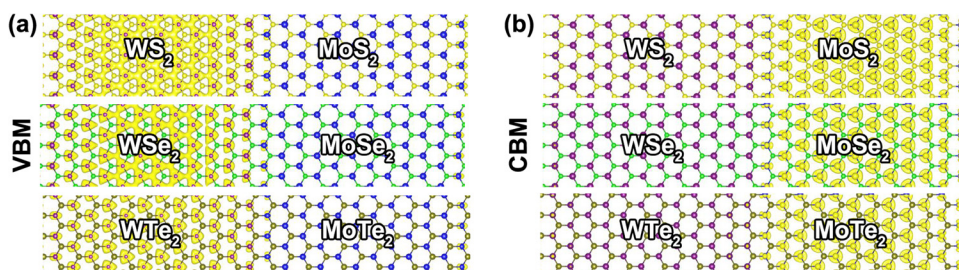


FIG. 3. Charge densities of VBM (a) and CBM (b) states for monolayer  $\text{WX}_2$ - $\text{MoX}_2$  lateral heterostructures with common X.

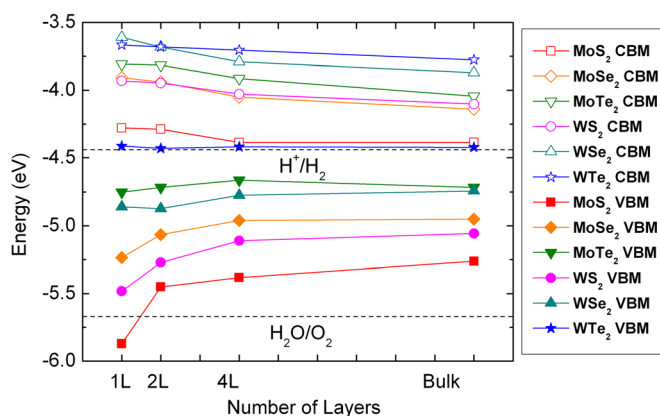


FIG. 4. Band edge positions of  $\text{MX}_2$  as a function of the number of layers calculated by PBE. The vacuum level is taken as zero reference. The dashed lines indicate the water redox potentials.

$\text{MX}_2$  monolayers studied here,  $\text{MoS}_2$  and  $\text{WS}_2$  meet this condition. The second requirement is that the photocatalyst must have suitable band edges to straddle the redox potentials of water. The standard water redox potentials with respect to the vacuum level are  $-4.44$  eV for the reduction ( $\text{H}^+/\text{H}_2$ ), and  $-5.67$  eV for the oxidation ( $\text{H}_2\text{O}/\text{O}_2$ ).<sup>25</sup> Jiang has shown that bulk  $\text{MX}_2$  cannot be applied directly to overall photo-splitting of water because their CBM or VBM positions are not suitable.<sup>16</sup> Our calculations show that indeed the CBMs (VBMs) of bulk  $\text{MoX}_2$  and  $\text{WX}_2$  are higher than the reduction (oxidation) potential (Fig. 4), so they can only be used for water reduction. However, according to Figs. 4(a), monolayer  $\text{MoS}_2$  satisfies this band edge requirement. The energy of VBM of  $\text{MoS}_2$  monolayer is calculated to be  $-5.87$  eV by PBE and  $-6.27$  eV by HSE06. Since PBE underestimates the bandgap while HSE06 overestimates, it is reasonable to expect that the actual VBM position of  $\text{MoS}_2$  monolayer lies between  $-5.87$  eV and  $-6.27$  eV, which is lower than the water oxidation potential. The CBMs of  $\text{MoS}_2$  calculated by PBE and HSE06 are both around  $-4.3$  eV, higher than the water reduction potential. Therefore,  $\text{MoS}_2$  monolayer is a good candidate for spontaneous photo-splitting of water. It should be noted that the idea of using nano  $\text{MoS}_2$  for  $\text{H}_2$  evolution is also proposed in several previous studies.<sup>26</sup> In these works, the activity of  $\text{MoS}_2$  is mostly related to edge states or vacancies, hence the defect levels play important roles. Our calculations show that  $\text{MoS}_2$  is suited for photo-splitting of water even in the absence of defects.

In summary, we have provided band offset calculations for various 2D semiconductors and investigated their elastic and electronic properties from first principles calculations. The calculated band offsets between  $\text{MX}_2$  reveal that as the atomic number of M or X increases, the CBM and VBM energy also increases, and the VBO is larger than the CBO for common-cation pairs. We further show that the CBM and VBM of  $\text{MX}_2$  originate from the repulsion between the cation

$d$  and anion  $p$  orbitals, and the chemical trends of the band offsets can be interpreted accordingly. The  $\text{MoX}_2$ - $\text{WX}_2$  lateral heterostructures have type-II band alignment, and are suited for optoelectronics and energy conversion, and  $\text{MoS}_2$  monolayer is a good candidate for spontaneous photo-splitting of water.

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